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INFORMATION DISCLOSURE
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First Named Inventor	Karl-Heinz Schuster
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Examiner Name	Steve Whitesell
Attorney Docket No.	SHN-146-A

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Cite No.	Document No.		Publication Date mm-dd-yyyy	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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EXAMINER	STEVEN WHITESSELL GARDIN
DATE CONSIDERED	07/01/2006

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not considered. Include a copy of this form with next communication to applicant.

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /S.W./